	Application No.	Applicant(s)	
Notice of Allowability	10/686,723	HASEGAWA ET AL	
	Examiner	Art Unit	
	Kripa Sagar	1756	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. This communication is responsive to <u>11/18/03</u> .			
2. 🔀 The allowed claim(s) is/are <u>1</u> .			
3. 🗵 The drawings filed on <u>17 October 2003</u> are accepted by the Examiner.			
4.			
<ul> <li>Attachment(s)</li> <li>1. ☑ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 10/17/03</li> <li>4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ul>	5. Notice of Informal F 6. Interview Summary Paper No./Mail Da 7. Examiner's Amend 8. Examiner's Statem 9. Other	r (PTO-413), te ment/Comment	

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## **DETAILED ACTION**

## Response to Amendment

The supplemental preliminary amendment filed 10/17/03 has been entered.
 Claim 1 is under consideration.

## Allowable Subject Matter

2. Claim 1 is allowed.

The following is an examiner's statement of reasons for allowance: The claim recites a mask comprising a substrate coated with an antistatic film and light shielding patterns formed of a metal and a resist film.

References teaching this combination could not be found.

US Pat. 5019485 to Nakamura et al. teaches (fig.3) forming an anti-static film on a substrate and coating it with a photoresist film which is imaged to form a light shielding pattern. There is no patterned metal light shielding film.

Japanese patents JP 05-289307 to Matsuo et al. JP 56-030129 to Ootori and JP 59-022050 to Machida. teach substitution of a conventional Cr-based opaque film on a mask with an organic resist to form light shielding patterns. Although Matsuo, for example, uses e-beam for patterning the organic resist film there is no disclosure of an antistatic film on the substrate.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kripa Sagar whose telephone number is 571-272-1392. The examiner can normally be reached on M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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